

The listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently Amended) A manufacturing method of a display device in a plasma treatment chamber comprising the step of:

partially forming a conductor film over a substrate;

forming a resist mask by use of liquid droplet jetting means, over the conductor film;

forming a wiring by partially etching the conductor film over the substrate by discharging a plasma to the plasma treatment chamber from a plasma treatment means having a plurality of reactive gas discharge ports and one set of electrodes contained therein for generating the plasma at a pressure of 5 to 800 Torr from a first reactive gas introduced to the plasma treatment means;

after switching the first reactive gas to a second reactive gas, partially ashing the resist mask by discharging a plasma to the plasma treatment chamber from the plasma treatment means in the plasma treatment chamber at the pressure of 5 to 800 Torr from the second reactive gas introduced to the plasma treatment means;

providing the plasma treatment means in the plasma treatment chamber;

providing one electrode of the set of electrodes which surrounds an other electrode of the set of electrodes; and

providing a distal portion of the one electrode of the set of electrodes being pointed toward the other electrode of the set of electrodes ,

wherein the distal portion of the one electrode of the set of electrodes has a sharp angle shape, and

wherein the first reactive gas is discharged from a specific part of the plurality of reactive gas discharge ports.

2. (Currently Amended) A manufacturing method of a display device in a plasma treatment chamber comprising the step of:

partially forming a conductor film over a substrate;

forming a resist mask by use of liquid droplet jetting means, over the conductor film;

forming a wiring by partially etching the conductor film over the substrate by discharging a plasma to the plasma treatment chamber from a plasma treatment means having a plurality of reactive gas discharge ports and a plurality of sets of electrodes contained therein for generating the plasma at a pressure of 5 to 800 Torr from a first reactive gas introduced to the plasma treatment means;

after switching the first reactive gas to a second reactive gas, partially ashing the resist mask by discharging a plasma to the plasma treatment chamber from the plasma treatment means in the plasma treatment chamber at the pressure of 5 to 800 Torr from the second reactive gas introduced to the plasma treatment means;

providing the plasma treatment means in the plasma treatment chamber;

providing one electrode of the plurality of sets of electrodes which surrounds an other electrode of the plurality of sets of electrodes, respectively; and

providing a distal portion of the one electrode of the plurality of sets of electrodes being pointed toward the other electrode of the plurality of sets of electrodes, respectively,

wherein the distal portion of the one electrode of the plurality of sets of electrodes has a sharp angle shape, and

wherein the first reactive gas is discharged from a specific part of the plurality of reactive gas discharge ports.

3. (Canceled)

4. (Currently Amended) A manufacturing method of a display device comprising the steps of:

forming a conductor film over a substrate;

forming a resist mask over the conductor film;

partially etching the conductor film at a pressure of 5 to 800 Torr by discharging a plasma to a plasma treatment chamber from a plasma treatment means having a plurality of reactive gas discharge ports and one set of electrodes contained therein for generating the plasma from a first reactive gas introduced to the plasma treatment means, over the resist mask thereby forming a wiring;

after switching the first reactive gas to a second reactive gas, partially ashing the resist mask by discharging a plasma to the plasma treatment chamber from the plasma treatment means in the plasma treatment chamber at the pressure of 5 to 800 Torr from the second reactive gas introduced to the plasma treatment means;

providing the plasma treatment means in the plasma treatment chamber;

providing one electrode of the set of electrodes which surrounds an other electrode of the set of electrodes; and

providing a distal portion of the one electrode of the set of electrodes being pointed toward the other electrode of the set of electrodes ,

wherein the distal portion of the one electrode of the set of electrodes has a sharp angle shape, and

wherein the first reactive gas is discharged from a specific part of the plurality of reactive gas discharge ports.

5. (Currently Amended) A manufacturing method of a display device comprising the steps of:

forming a conductor film over a substrate;

forming a resist mask over the conductor film;

partially etching the conductor film at a pressure of 5 to 800 Torr by discharging a plasma to a plasma treatment chamber from a plasma treatment means having a plurality of reactive gas discharge ports and a plurality of sets of electrodes contained therein for generating the plasma from a first reactive gas introduced to the plasma treatment means, over the resist mask thereby forming a wiring;

after switching the first reactive gas to a second reactive gas, partially ashing the resist mask by discharging a plasma to the plasma treatment chamber from the plasma treatment means in the plasma treatment chamber at the pressure of 5 to 800 Torr from the second reactive gas introduced to the plasma treatment means;

providing the plasma treatment means in the plasma treatment chamber;

providing one electrode of the plurality of sets of electrodes which surrounds an other electrode of the plurality of sets of electrodes, respectively; and

providing a distal portion of the one electrode of the plurality of sets of electrodes being

pointed toward the other electrode of the plurality of sets of electrodes , respectively,

wherein the distal portion of the one electrode of the plurality of sets of electrodes has a sharp angle shape, and

wherein the first reactive gas is discharged from a specific part of the plurality of reactive gas discharge ports.

6. (Previously Presented) The manufacturing method of the display device according to any of claims 1, 2, 4 and 5, wherein the substrate has a size of 1,000 x 1,200 mm² or more.

7. (Previously Presented) The manufacturing method of the display device according to any of claims 1, 2, 4 and 5, wherein the plasma treatment means scans the substrate in one direction.

8. (Previously Presented) The manufacturing method of the display device according to any of claims 1, 2, 4 and 5, wherein the plasma treatment means alternately scans the substrate in a row direction and in a column direction.

9. (Previously Presented) The manufacturing method of the display device according to any of claims 4 and 5, wherein the resist mask is formed by use of liquid droplet jetting means.

10.-11. (Canceled)

12. (Previously Presented) The manufacturing method of the display device according to any of claims 1, 2, 4 and 5, further comprising:

moving the plasma treatment means along a rail.